

IN THE ABSTRACT:

Please amend the abstract as follows.

-- Two independent fine adjustment stages (~~62, 72~~) are arranged on one coarse adjustment stage (~~73~~) to simultaneously perform all of focus measurement and part of alignment measurement in parallel with an exposure operation. A method of transporting a wafer together with a chuck is adopted as a precondition. Alignment of a pattern on a wafer (~~60~~) with a chuck (~~61~~) is performed before the chuck is mounted on each fine adjustment stage. --